

AMENDMENTS TO THE CLAIMS:

The following listing of claims replaces all prior lists, and all prior versions, of claims in the application:

Listing of Claims:

1. (currently amended) A photomask comprising:

light-shielding patterns formed of a metal for integrated circuit pattern

transfer; and

light-shielding patterns formed of a resist film for the integrated circuit pattern transfer,

both said light-shielding patterns formed of a metal and said light-shielding patterns formed of a resist film being provided over a mask substrate, and wherein an antistatic film is provided over the mask substrate.